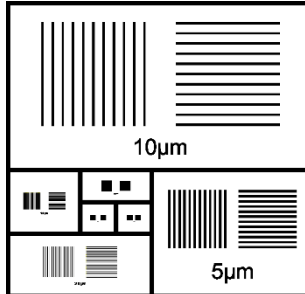
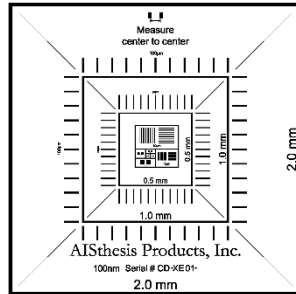


# AISthesis Products, Inc.

Advanced Imaging Products for Nanotechnology, Engineering and Life Sciences

## Wafer Level Certificate of Traceability for Pelcotec™ XY-Critical Dimension Standard



Product Number: **Pelcotec™ 685-01 CDMS-XY-0.1T**

Manufactured for and Distributed by:

Product Description: 2.5x2.5mm **Pelcotec™ 2mm-100nm XY-Critical Dimension Magnification Standard**



Wafer Identifier: CD-XE01

The accuracy of these products was determined by reference comparison to working standards traceable to the National Institute of Standards and Technology (NIST), Test No. 861/280822-11.

Line	Direction	Average pitch of wafer	Number of lines averaged	Average pitch uniformity (1 $\sigma$ uncertainty)	Total expanded uncertainty (3 $\sigma$ ) average pitch for wafer*
2.0mm	X/Y	2.00 mm	2	$\pm 2 \mu\text{m}$ ( $\pm 0.10\%$ )	$\pm 7 \mu\text{m}$ ( $\pm 0.35\%$ )
1.0mm	X/Y	1.00 mm	2	$\pm 1 \mu\text{m}$ ( $\pm 0.10\%$ )	$\pm 3.5 \mu\text{m}$ ( $\pm 0.35\%$ )
0.5mm	X/Y	0.500 mm	2	$\pm 0.5 \mu\text{m}$ ( $\pm 0.10\%$ )	$\pm 1.75 \mu\text{m}$ ( $\pm 0.35\%$ )
0.10mm	X/Y	0.100 mm	11	$\pm 0.10 \mu\text{m}$ ( $\pm 0.10\%$ )	$\pm 0.35 \mu\text{m}$ ( $\pm 0.35\%$ )
50 $\mu\text{m}$	X/Y	50.00 $\mu\text{m}$	11	$\pm 0.05 \mu\text{m}$ ( $\pm 0.10\%$ )	$\pm 0.175 \mu\text{m}$ ( $\pm 0.35\%$ )
10 $\mu\text{m}$	X/Y	10.00 $\mu\text{m}$	11	$\pm 0.01 \mu\text{m}$ ( $\pm 0.10\%$ )	$\pm 0.035 \mu\text{m}$ ( $\pm 0.35\%$ )
5 $\mu\text{m}$	X/Y	5.00 $\mu\text{m}$	2	$\pm 0.01 \mu\text{m}$ ( $\pm 0.20\%$ )	$\pm 0.035 \mu\text{m}$ ( $\pm 0.70\%$ )
2 $\mu\text{m}$	X/Y	2.00 $\mu\text{m}$	1	$\pm 0.004 \mu\text{m}$ ( $\pm 0.20\%$ )	$\pm 0.014 \mu\text{m}$ ( $\pm 0.70\%$ )
1 $\mu\text{m}$	X/Y	1.00 $\mu\text{m}$	17	$\pm 0.002 \mu\text{m}$ ( $\pm 0.20\%$ )	$\pm 0.007 \mu\text{m}$ ( $\pm 0.70\%$ )
500nm	X/Y	500.8 nm	20	$\pm 1.00 \text{ nm}$ ( $\pm 0.20\%$ )	$\pm 3.5 \text{ nm}$ ( $\pm 0.70\%$ )
250nm	X/Y	250.7 nm	21	$\pm 0.50 \text{ nm}$ ( $\pm 0.20\%$ )	$\pm 1.75 \text{ nm}$ ( $\pm 0.70\%$ )
100nm	X/Y	100.3 nm	52	$\pm 0.20 \text{ nm}$ ( $\pm 0.20\%$ )	$\pm 0.75 \text{ nm}$ ( $\pm 0.70\%$ )

\* The 3 $\sigma$  uncertainty (99.73% confidence interval) average pitch is determined using a minimum of nine die per production wafer. Each average pitch is determined using 100+ measurements on each die averaged over the stated number of lines. The total expanded uncertainty includes both Type A and Type B uncertainties corrected for sample size using an appropriate Student t-factor.

Equipment used:

Instrument	Model number	Serial #	NIST Certified CD/Recalibration	Resolution	Repeatability
FE-SEM	FEI Verios	9922551	CD-PG01-0211/June 2018	0.9nm	0.03%

D.S. Finch  
Certified by

Signature

February 7<sup>th</sup>, 2018  
Date

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